



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of: **Miwa KOZAWA et al.**

Group Art Unit: **1752**

Serial Number: **10/629,806**

Examiner: **LEE, SIN J**

Filed: **July 30, 2003**

P.T.O. Confirmation No.: **9494**

For: **RESIST PATTERN THICKENING MATERIAL, PROCESS FOR FORMING  
RESIST PATTERN, AND PROCESS FOR MANUFACTURING  
SEMICONDUCTOR DEVICE**

Attorney Docket No.: **030923**

Customer Number: **38834**

**DECLARATION UNDER 37 CFR 1.132**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

August 25, 2004

Sir:

We, Miwa Kozawa, Koji Nozaki, Takahisa Namiki and Junichi Kon, hereby declare and state that:

- (1) We are Japanese citizens.
- (2) We have been engaged in research of a resist pattern material at Fujitsu Limited, located at 1-1, Kamikodanaka 4-chome, Nakahara-ku, Kawasaki-shi, Kanagawa 211-8588 Japan.
- (3) We are the inventors of United States Patent Application Serial No. 10/629,806, filed on July 30, 2003, and also familiar with the content of the cited reference to Nozaki et al (United States Patent Application Publication No. 2003/0102285).

Application No. 10/629,806  
Declaration under 37CFR1.132

(4) We are named as coinventors of United States Patent Application Publication No. 2003/0102285.

(5) United States Patent Application Serial No. 10/629,806 and United States Patent Application Publication No. 2003/0102285 were assigned to the same company, Fujitsu Limited.

(6) We conceived or invented the subject matter declared in United States Patent Application Publication No. 2003/0102285 and relied on in the rejection.

(7) We hereby declare that all statements made herein of our own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like are punishable by fine or imprisonment, or both, under the laws of the United State and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

Miwa Kozawa  
Miwa Kozawa

2004/8/20  
Date

Koji Nozaki  
Koji Nozaki,

2004/8/20  
Date

Takahisa Namiki  
Takahisa Namiki

2004/8/20  
Date

Junichi Kon  
Junichi Kon

2004/8/20  
Date